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SHIGA7.040APC

IAP20 R&D PCT.PTO 22 DEC 2005 PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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|----------------|---|---|
| Applicant | : | Hayashi et al. |
| Appl. No. | : | Unknown |
| Filed | : | Herewith |
| For | : | POSITIVE RESIST COMPOSITION AND METHOD OF FORMING RESIST PATTERN USING SAME (as amended) |
| Examiner | : | Unknown |
| Group Art Unit | : | Unknown |

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

Preliminary to examination on the merits, please amend the above-captions U.S. National
Phase Application as follows:

Amendments to the Specification begin on page 2 of this paper.

Remarks/Arguments begin on page 3 of this paper.